IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Akio SUGI, et al.

Serial No.: NEW APPLICATION

Group Art Unit:

Filed: November 24, 2003

Examiner:

For:

SEMICONDUCTOR DEVICE AND METHOD OF MANUFACTURING THE DEVICE

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. §1.56, the attention of the Patent and Trademark Office is hereby

directed to the references listed on the attached Form PTO-1449. Copies of the references listed on

Form PTO-1449 are attached.

It is respectfully requested that the information be expressly considered during the

prosecution of this application, that these references be made of record therein and appear among

the "References Cited" on any patent to issue therefrom, and that an initialed copy of the PTO-1449

be returned to the undersigned.

Respectfully submitted,

Date: 1 - 24 - 63

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Sheet, 1	of	1								
INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)				Docket Number (Optional) FUJI:280 . SERIAL			NO.: NEW APPLICATION			
				APPLICANT(s) Akio SUGI et al.						
				FILING DATE: November 24, 2003			Group Art Unit			
U.S. PATENT DOCUMENTS										
EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CL	ASS	SUBCLASS	FILING DATE IF APPROPRIATE		
	US	2002/0179967	12/02	Fujishima	257		330			
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FOREIGN PATENT DOCUMENTS										
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLA	ASS	SUBCLASS	TRANSLATION YES NO		
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	<u> </u>	0.	THER DOCU	MENT(S) (Including Author, Title, Date, Pe	ertinent Pages	, Etc.)				
	"A 30V Class Extremely Low On-resistance Meshed Trench Lateral Power MOSFET"; A SUGI et al.; IEEE 9/2002; pp. 297-300									
EXAMINER		DATE CONSIDERED								

^{*}EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.